

LISTING OF THE CURRENT CLAIMS
IN ACCORDANCE WITH REVISED AMENDMENT PRACTICE

Claims 1-11: Previously Withdrawn

Claims 12-19: Canceled.

Claim 20: (Original) A method of removing a spin-on compound, comprising:
spin-depositing a spin-on compound on a surface of a substrate, wherein the spin-on compound comprises silicon, wherein the first solvent comprises propyl acetate, and wherein the second solvent comprises ethyl lactate; and
spin-rinsing the spin-on compound with a solvent mixture, wherein the solvent mixture comprises a first solvent that dissolves the spin-on compound, and a second solvent that is inert to the spin-on compound.

Claims 21-23: Previously Canceled.

Claim 24: (Previously Added) The method of claim 20, wherein the substrate comprises a trench.

Claim 25: (Previously Added) The method of claim 24, wherein the spin-on compound is spin-deposited into the trench.

Claim 26: (Previously Added) The method of claim 20, wherein the spin-on compound is partially removed.

Claim 27: (Canceled) A method of forming a shallow trench isolation structure, comprising:
partially removing the spin-on compound according to the method of claim 20 such that an upper surface of the remaining compound is below the surface of the substrate;
depositing a second compound onto the substrate surface and onto the upper surface of the remaining spin-on compound by chemical vapor deposition.

- Claim 28: (Canceled) The method of claim 27, further comprising planarizing the isolation structure such that the surface of the substrate and an upper surface of the second compound are substantially coplanar.
- Claim 29: (Canceled) The method of claim 27, wherein the substrate surface and the trench further comprise a thermal oxide coat.
- Claim 30: (Amended) The method of claim 20 ~~one of claims 20 or 27~~, wherein the spin-on compound is formed from at least one compound selected from the group consisting of methylsilsesquioxane, hydrogensilsesquioxane, methylhydridosilsesquioxane, silicate, and perhydrosilazane.
- Claim 31: (Canceled) The method of claim 27, wherein the second compound is formed from tetraethylorthosilicate or silane.